

PCMPC 2017

Post CMP Cleaning Conference
SPCC2017 Special Event

Agenda

Monday — March 27, 2017

Amphitheatre 204

8:00 am – 10:00 am: Registration and Networking

Session 1: Market Trends

10:00 AM: Introductions, Welcome, Conference Overview — Mark Thirsk

10:15 AM: KEYNOTE: Hong Jin Kim – GlobalFoundries
CMP Technological Paradigm Shift to Surface Cleaning

11:30 AM: JinGoo Park – Han Yang University
Post CMP Surface Preparation in sub 10nm Devices

12:00 PM - 1:00 PM LUNCH

Location: Tejas Restaurant

Session 2: Materials & Process Trends

1:00 PM: Entegris – Michael White
Challenges and Mechanistic Aspects for Advanced Post CMP Cleaners

1:30 PM: Dnyanesh Tamboli - Versum Materials
Enabling Low Defectivity Solutions Through Co-Development of CMP Slurries and Cleaning Solutions for Cobalt Interconnect Applications

2:00 PM: Iqbal Ali – Linx Consulting
CMP Defects and Evolution of PCMP Cleans

2:30 PM: Viorel.Balan - CEA

3:00 PM – 3:30 PM COFFEE

Location: Courtyard Terrace

Session 3: Equipment & Process Trends

3:30 PM: Ekaterina Mikhaylichenko - Applied Materials
High Shear Force Chemical Mechanic Cleaning for CMP Defect Reduction

4:00 PM: Cass Shang – DuPont EKC Technology
Development of PCMP Cleaner for both Tungsten and Cobalt Applications

4:30PM: Ratanak Yim – CEA

5:00 PM – 6:30 PM NETWORKING

Location: Courtyard Terrace